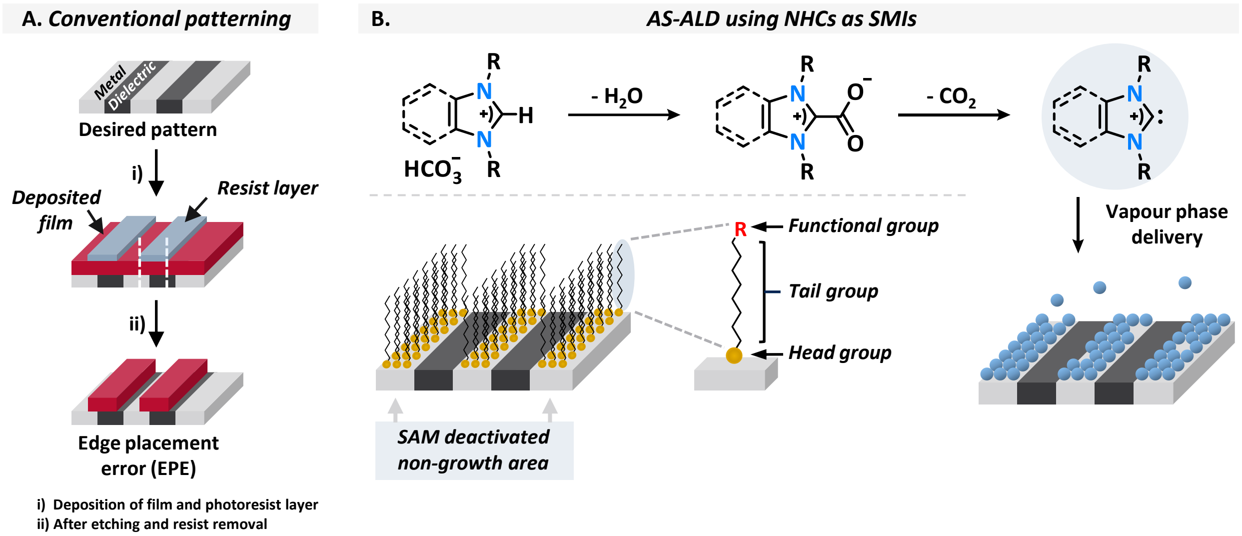

Figure 1: a) Comparison between A) conventional etch/lithographic patterning and B) AS-ALD fabrication methods with NHCs generated in situ through controlled thermolysis.

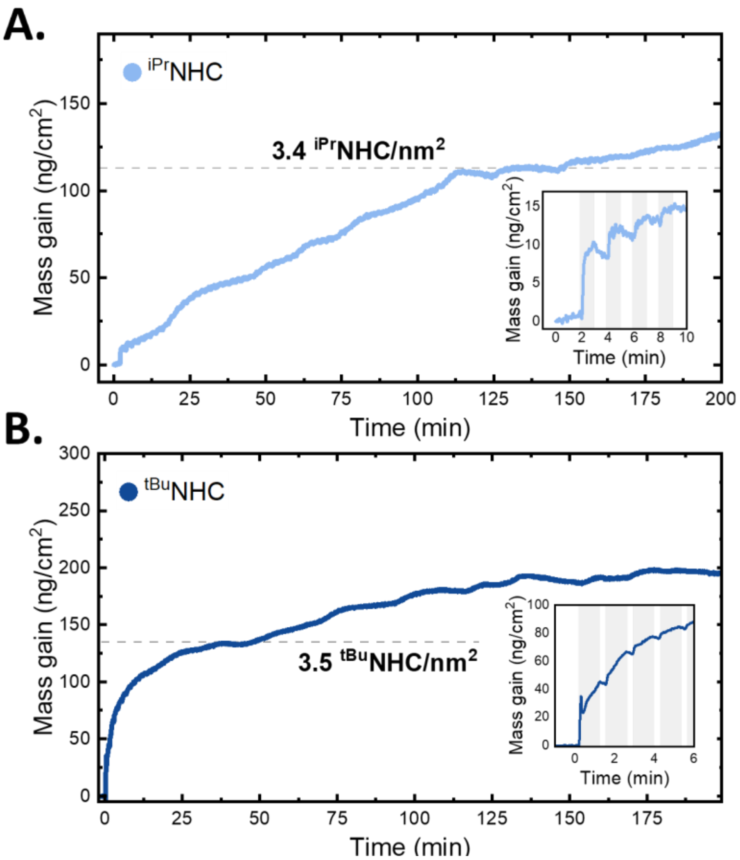

Figure 2: Pulsed exposure QCM experiments demonstrating saturative behaviour for A) 100 cycles of (60s ^{iPr}NHC, 60s purge) and B) 100 cycles of (60s ^{tBu}NHC, 20s purge)